

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

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| Session Title: | [WD1] EUV Mask, Pellicle, Resist III |
| Session Date: | November 16 (Wed.), 2022 |
| Session Time: | 10:45-11:55 |
| Session Room: | Room D (Sidney Room, 2F) |
| Session Chair: | Prof. Hyun-Dam Jeong (Chonnam Nat'l Univ., Korea) Research Fellow, Jeonglim Nam (Hanyang Univ., Korea) |

[WD1-1] [Invited] 10:45-11:15

EUV Under-Layer Development and Challenges

Mamoru Tamura, Ryuta Mizuochi, Hiroto Ogata, Shun Kubodera, Sho Shimizu, Yuki Kato, Kosuke Igata, Kohei Itaoka, Makoto Nakajima, and Rikimaru Sakamoto (Nissan Chemical Corp., Japan)

[WD1-2] 11:15-11:35

Dependency of Interfacial Characteristics of [Mo/Si]₄₀ Multi-Layer on Sputtering DC Gun Power for High Reflectance of EUV Blank Mask

Han-Sol Jun, So-Hyun Lee, Ho-Jung Kwon, Yo-Han Choi, Jin-Young Choi, Tae-Hun Shim, and Jea-Gun Park (Hanyang Univ., Korea)

[WD1-3] 11:35-11:55

Damage-Free Pinpoint Particle Removal from a EUV Exposed Pellicle

Hyun-gyu Kang, Dong-hyeon Kwon, Tae-gon Kim, Jin-ho Ahn, Byung-hoon Lee, and Jin-Goo Park (Hanyang Univ., Korea)